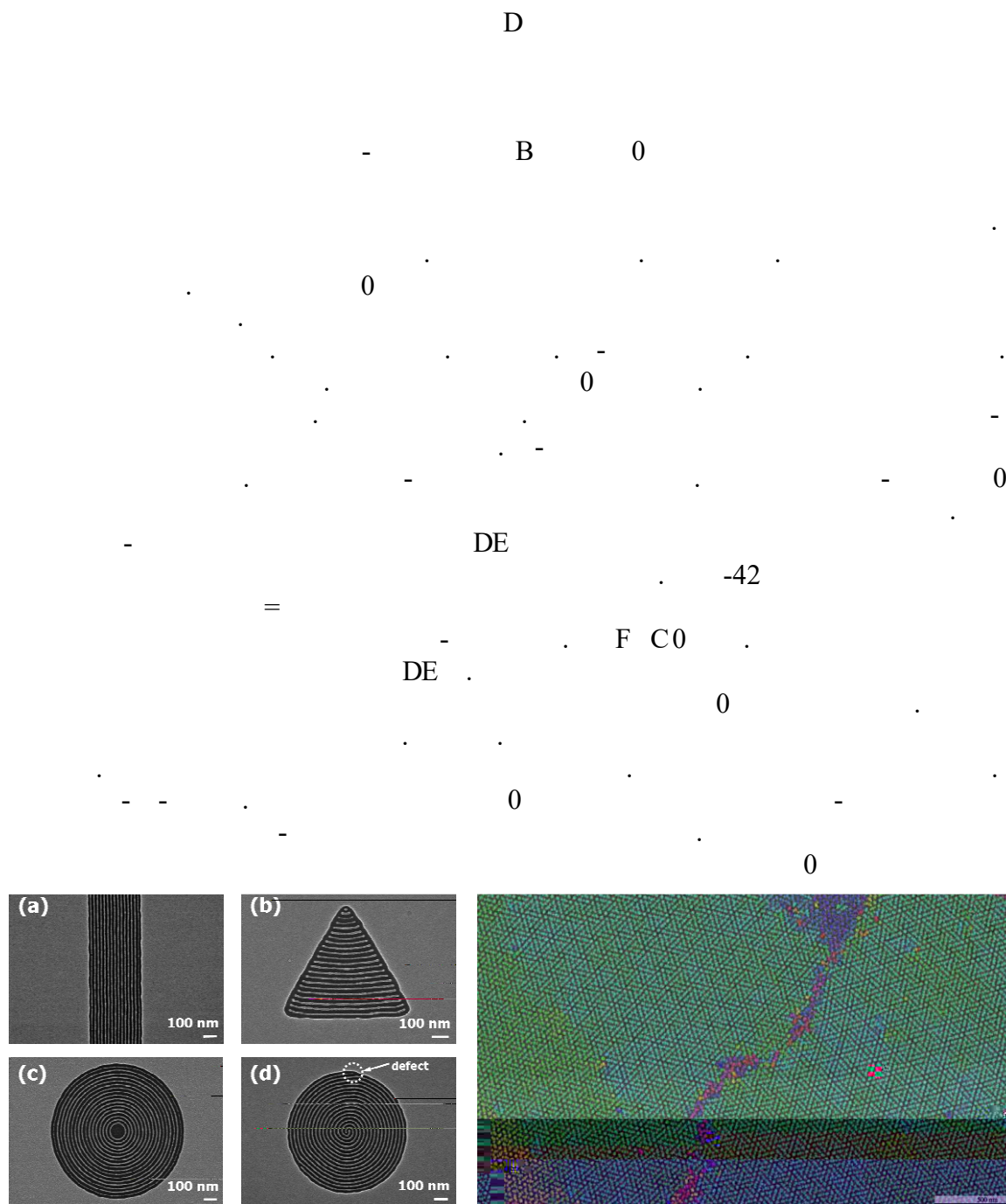


Directed Self-Assembly for Nanolithography: Writing with Polymers



Left: H

Right

1. Jin, C.; Olsen, B. C.; Luber, E. J.; Buriak, J. M. Preferential Alignment of Incommensurate Block Copolymer Dot Arrays Forming Moiré Superstructures. *ACS Nano*, **2017**, *11*, 3237-3246.
2. Jin, C.; Olsen, B. C.; Luber, E. J.; Buriak, J. M. Nanopatterning via Solvent Vapor Annealing of Block Copolymer Thin Films. *Chem. Mater.*, **2017**, *29*, 176-188.